



Form 1-49 (Modified)

Information Disclosure
Statement By Applicant

(Use Several Sheets if Necessary)

Atty Docket No.

MAT-4

Applicants:

Rene George et al

Filing Date

9/17/03

Serial No.:

10/665,267

Group

4763 2813

U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
HJD	A	US 6,524,936 B2	2/25/03	Hallock et al			
HJD	B	US 6,342,446 B1	1/29/2003	Smith et al			
HJD	C	US 6,426,304 B1	6/30/2002	Chien et al			
HJD	D	US 6,379,576 B2	4/30/2002	Luo et al			
HJD	E	US 6,352,936 B1	3/5/2002	Jehoul et al			
HJD	F	US 6,342,446 B1	1/29/2002	Smith et al			
HJD	G	US 6,277,733 B1	8/21/2001	Smith			
HJD	H	US 6,251,771 B1	6/26/2001	Smith et al			
HJD	I	5,628,871	5/13/1997	Shinagawa			
HJD	J	5,534,231	7/9/1996	Savas			
HJD	K	5,403,436	4/4/1995	Fujimura et al			
HJD	L	4,980,022	12/25/1990	Fujimura et al			
HJD	M	4,861,732	8/29/1989	Fujimura et al			
HJD	N	4,861,424	8/29/1989	Fujimura et al			

Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
✓	○							

Other Documents

Examiner	No.	Author, Title, Date, Place (e.g. Journal) of Publication
HJD	P	Boumerzoug et al, A Dry Process For Polymer Sidewall Residue Removal After Via-Hole Etching, 11/12/2000, 1-1 st Annual IEEE/SEMI Advanced Semiconductor Manufacturing Conference and Workshop, Boston, MA (ASMC 2000)
HJD	Q	Xu et al, Dry Cleaning Technologies For Post Metal And Via Applications, 7/13/1998, Symposium on Contamination Free Manufacturing for Semiconductor Processing, Semicon West 98, San Francisco, CA.
HJD	R	Hu et al, Resist Stripping for Multilevel Interconnect Integrating Low k Dielectric Material, 2/2000, AVS First International Conference on Microelectronics and Interfaces.
HJD	S	Gooch et al, Elimination Solvents From Semiconductor Wafer Manufacturing, 7/1/1999, 3 rd Green Chemistry and Engineering Conference, Washington DC.
HJD	T	Dopp et al, Manufacturing Qualifications of an All-Dry Via Deveil Plasma Process, 5/2000, 197 th Electrochemical Society Meeting, Toronto, Canada.
Examiner		Date Considered
	Neaver Ory	10/21/05

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.



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Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
HJ	A	US2002/0110992 A1	8/15/2002	Ho			

Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No

Other Documents

Examiner							
Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication					

Examiner	Date Considered
<i>Heather Doty</i>	<i>10/20/05</i>

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U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
H	A	US2002/0110992 A1	8/15/2002	Ho			
H	B	5,770,100	6/23/1998	Fukuyama			
H	C	US 6,265,320 B1	7/24/2001	Shi et al			

Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Yes	No

Other Documents

Examiner		
Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
Examiner		Date Considered
<i>Heather A. Doty</i>		<i>10/20/05</i>

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